



PATENT
Docket No. 150.00560102

#4/8
4/6/01

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant(s): Whonchee Lee et al.) Group Art Unit: 1765
Serial No.: 09/560,268) Examiner: D. Deo
Filed: April 26, 2000)
For: METHOD AND COMPOSITION FOR SELECTIVELY ETCHING AGAINST
COBALT SILICIDE

AMENDMENT AND RESPONSE

Assistant Commissioner for Patents
Washington D.C. 20231

Dear Sir:

In response to the Office Action mailed December 28, 2000, please consider the following remarks and amendments to the application.

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In the Claims

Please cancel claim 36; amend claims 37-39; and add new claims 46-63. The new and amended claims are provided below in clean form. Per 37 C.F.R. § 1.121, amended claims are also shown in Appendix A with notations to indicate changes made (for convenience, all pending claims, including those new claims added hereby, are provided in Appendix A).

37. (Once Amended) The etching composition according to claim 38, wherein the mineral acid is HCl and the peroxide is hydrogen peroxide.

38. (Once Amended) An etching composition, the composition comprising a mineral acid, a peroxide, and deionized water at a ratio in a range of about 1:1:35 (mineral acid:peroxide:deionized water) to about 1:1:5 (mineral acid:peroxide:deionized water).

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